

WEST

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Term:

L34 not (optical near5 head\$3)

Display: Documents in Display Format: Starting with Number Generate: ☐ Hit List ☒ Hit Count ☐ Side by Side ☐ Image

Search

Clear

Help

Logout

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Main Menu

Show S Numbers

Edit S Numbers

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DATE: Tuesday, March 05, 2002 [Printable Copy](#) [Create Case](#)Set Name Query

side by side

Hit Count Set Name

result set

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<u>L35</u>	L34 not (optical near5 head\$3)	120	<u>L35</u>
<u>L34</u>	L33 and l32	138	<u>L34</u>
<u>L33</u>	(hologra\$6).ti.	14740	<u>L33</u>
<u>L32</u>	((support\$1 or substrate\$1) with (semiconductor\$4 or wafer\$1))	340981	<u>L32</u>
<u>L31</u>	((support\$1 or substrate\$1) near15 (semiconductor\$4 or wafer\$1))	330634	<u>L31</u>
<u>L30</u>	(L23 and l22) not l29	24	<u>L30</u>
<u>L29</u>	L23 same l22	18	<u>L29</u>
<u>L28</u>	L25 and l22	132	<u>L28</u>
<u>L27</u>	L26 and l23	42	<u>L27</u>
<u>L26</u>	L25 and l20	155	<u>L26</u>
<u>L25</u>	(hologra\$6).ab.	22255	<u>L25</u>
<u>L24</u>	L23 and l20	57	<u>L24</u>

<u>L23</u>	((hologra\$6) near5 (recording or photosensitive))	7018	<u>L23</u>
<u>L22</u>	((hologra\$6) with ((support\$1 or substrate\$1) near10 (semiconductor\$4)))	178	<u>L22</u>
<u>L21</u>	((hologra\$6) with ((support\$1 or substrate\$1) near15 (semiconductor\$4)))	197	<u>L21</u>
<u>L20</u>	((hologra\$6) with ((support\$1 or substrate\$1) near15 (semiconductor\$4 or wafer\$1)))	225	<u>L20</u>
<u>L19</u>	L18 same l17	11	<u>L19</u>
<u>L18</u>	((hologra\$6) same ((support\$1 or substrate\$1) with (semiconductor\$4)))	356	<u>L18</u>
<u>L17</u>	((hologra\$6) same ((support\$1 or substrate\$1) with (wafer\$1)))	62	<u>L17</u>
<u>L16</u>	((hologra\$6) same ((support\$1 or substrate\$1) with (semiconductor\$4 or wafer\$1)))	402	<u>L16</u>
<u>L15</u>	((hologra\$6) same ((support\$1 or substrate\$1) with (semiconductor\$4 or silicon or wafer\$1)))	487	<u>L15</u>
<u>L14</u>	((hologra\$6) same ((support\$1 or substrate\$1) with (semiconductor\$4 or silicon)))	465	<u>L14</u>
<u>L13</u>	L12 and l10	38	<u>L13</u>
<u>L12</u>	(resist\$2 or photoresist\$2) same ((halation or antihalation) near4 (layer\$1 or film\$1))	145	<u>L12</u>
<u>L11</u>	L10 and l9	74	<u>L11</u>
<u>L10</u>	((hologra\$6 or resist\$2 or photoresist\$2) near5 (decal\$4 or dry))	11854	<u>L10</u>
<u>L9</u>	(resist\$2 or photoresist\$2) same (halation or antihalation)	594	<u>L9</u>
<u>L8</u>	L7 or l4	49	<u>L8</u>
<u>L7</u>	L6 and l5	25	<u>L7</u>
<u>L6</u>	((hologra\$6 or resist\$2 or photoresist\$2) near5 (peel\$4 or releas\$6 or laminat\$6))	16313	<u>L6</u>
<u>L5</u>	((hologra\$6 or resist\$2 or photoresist\$2) near5 (decal\$4))	76	<u>L5</u>
<u>L4</u>	L3 and l1	24	<u>L4</u>
<u>L3</u>	((feed or feeding) with (support\$2 or substrate\$2 or wafer\$1))	92096	<u>L3</u>
<u>L2</u>	((feed or feeding) with (support\$2 or substrate\$2))	88169	<u>L2</u>
<u>L1</u>	((peel\$3 or releas\$6) same (hologra\$6 or resist\$2 or photoresist\$2)) and (((feed or feeding) with (sheet\$1 or cut))same (hologra\$6 or resist\$2 or photoresist\$2)))	120	<u>L1</u>

END OF SEARCH HISTORY